



Synthesis and grafting of n and p type σ - π - σ systems on substrates for molecular electronic applications.

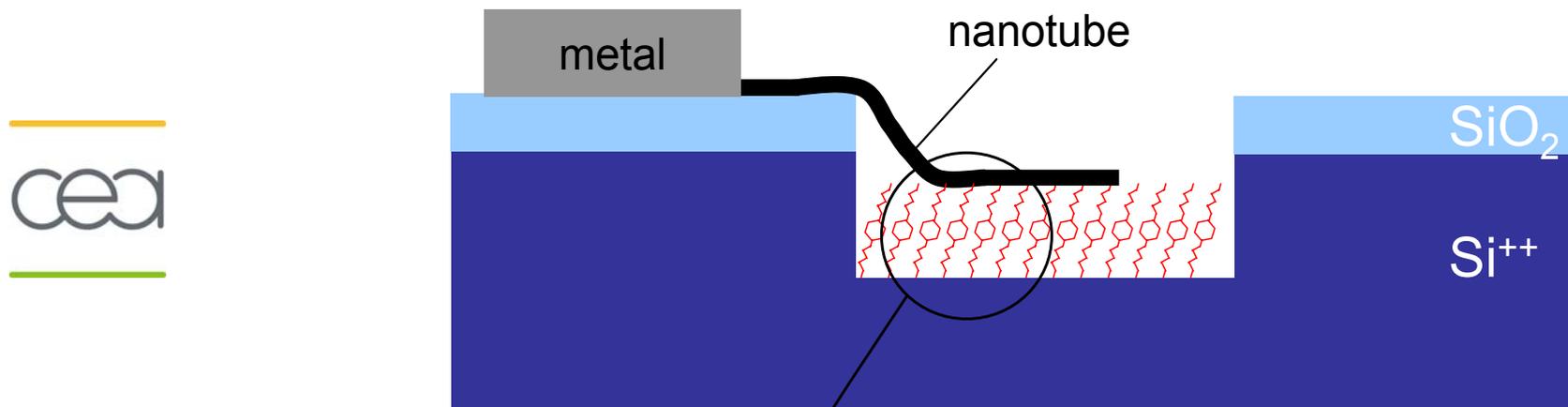


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Vincent Derycke, Jean-Philippe Bourgoïn and Serge Palacin
CEA-Saclay IRAMIS/SPCSI and SPEC

ANR MEMO project

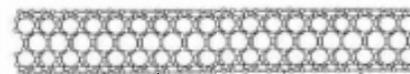
Dinesh K. Aswal, J V. Yakhmi
Bhabha Atomic Research Centre
Coll. CEA-DAE

Structure of the molecular diode : Nanotube / Molecules / Silicon

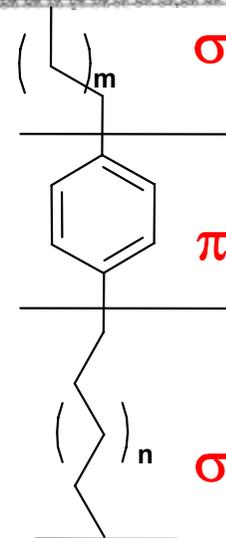


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- (1) Connect few molecules
- (2) Avoid metal evaporation to contact the molecules
- (3) Prove a negative differential resistance effect at room temperature



SWNTs

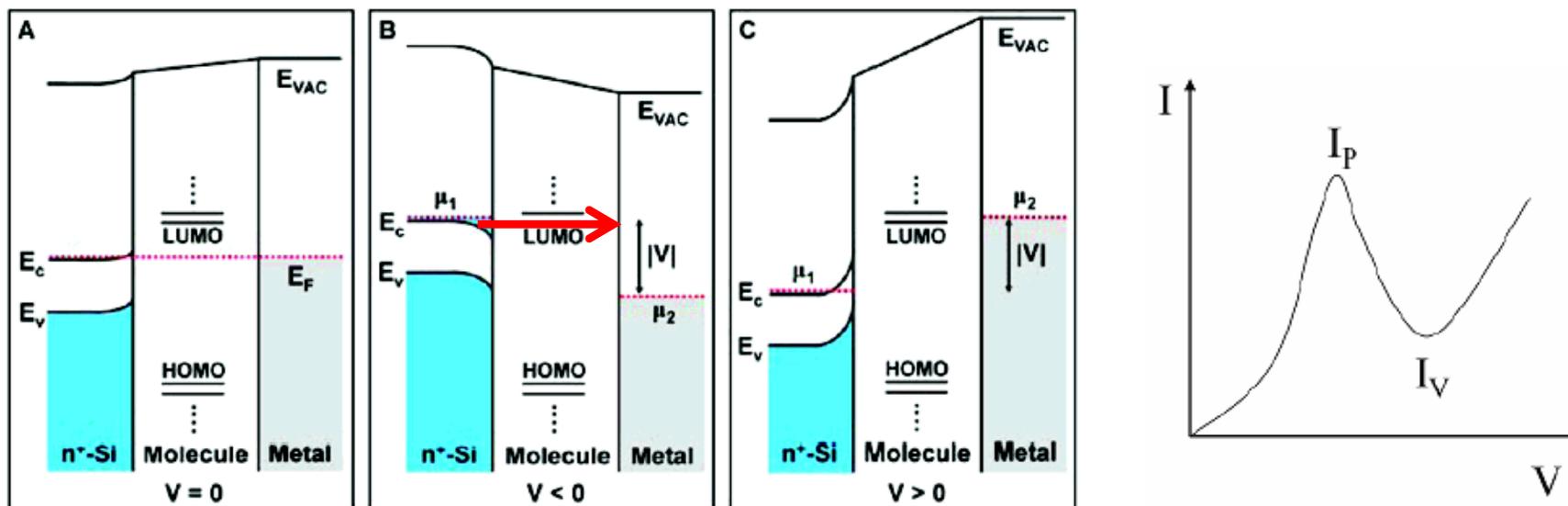


Silicon

σ : alkyl-chains act as tunnel barriers

π : conjugated part acts as the potential well

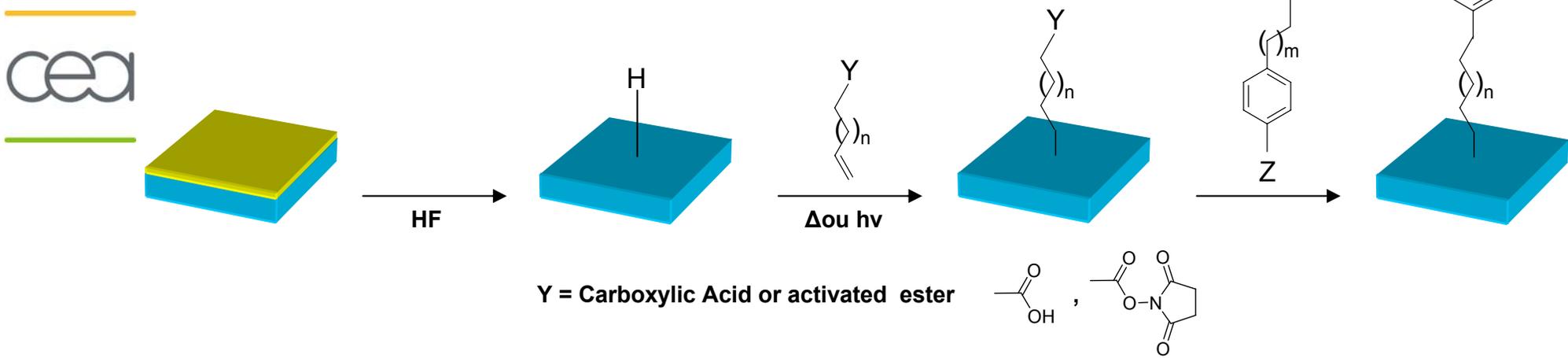
negative differential resistance (NDR) effect



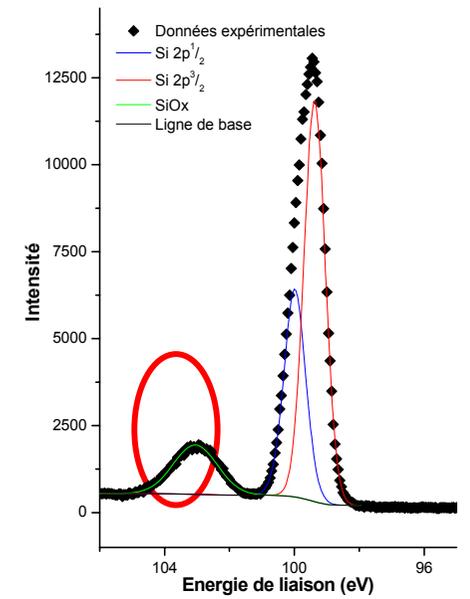
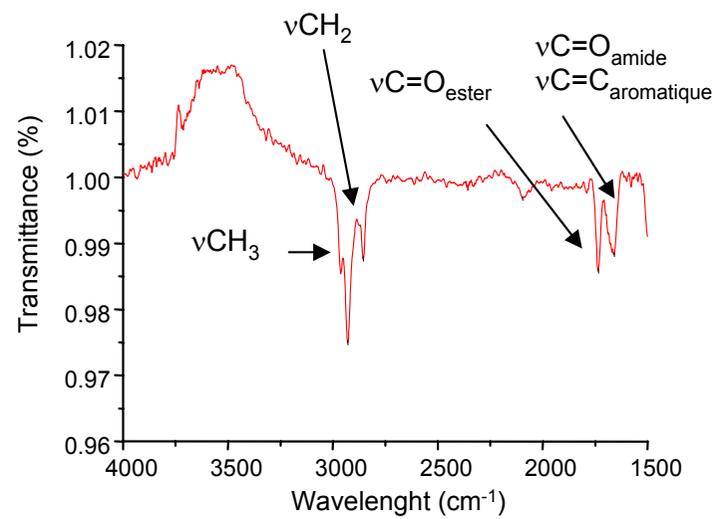
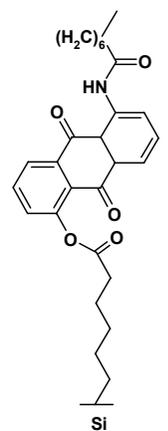
NDR peak should appear whenever an energy level of the molecule comes into resonance with the electrons of the conduction band of the silicon or holes in the valence band of the silicon.

Sequential synthesis of a σ - π - σ monolayer on silicon (L. Baraton Ph. D Thesis)

Post-functionalization way



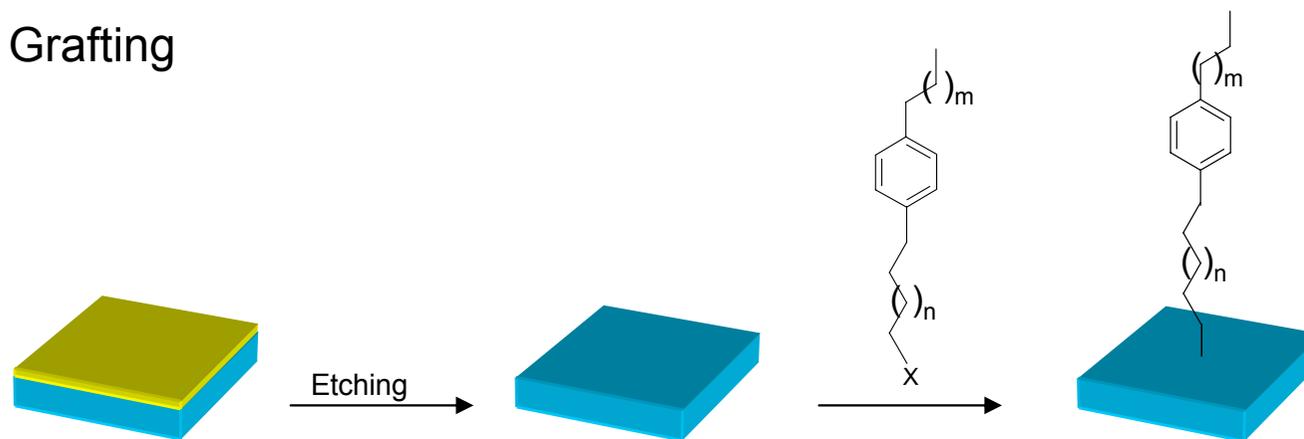
Esterification reaction on a monolayer



Approach used in the project

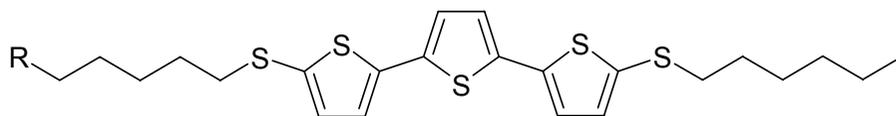
Direct Grafting

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Chosen compounds

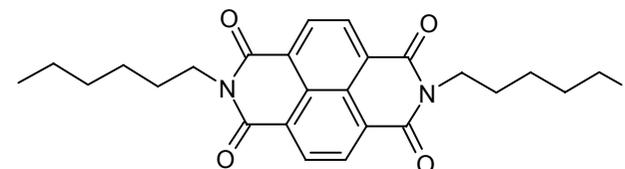
Terthiophene derivative



R = CH=CH₂, CH₂SH

Electron donor (p-type)

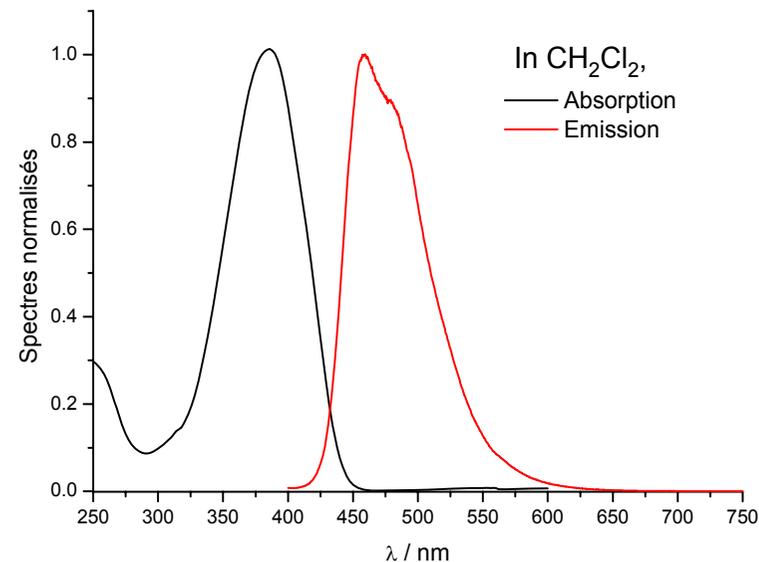
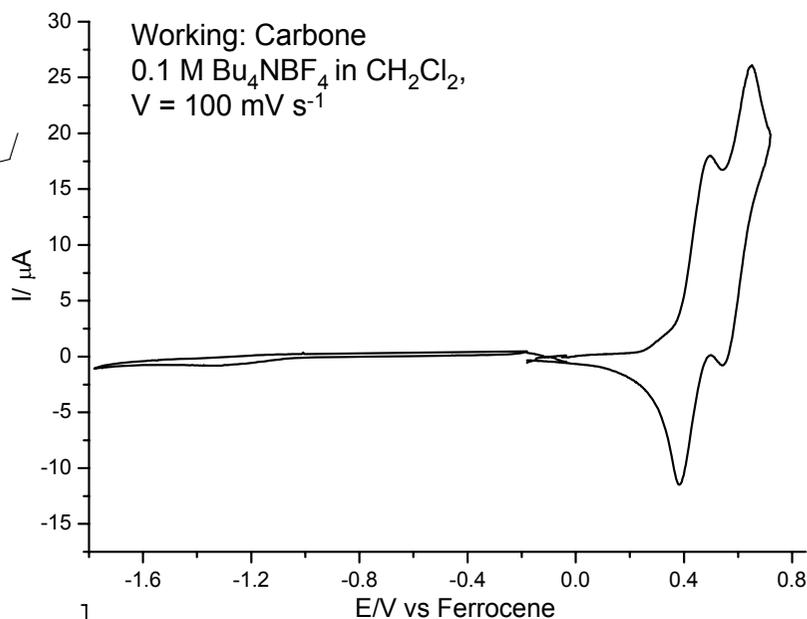
Naphthalene derivative



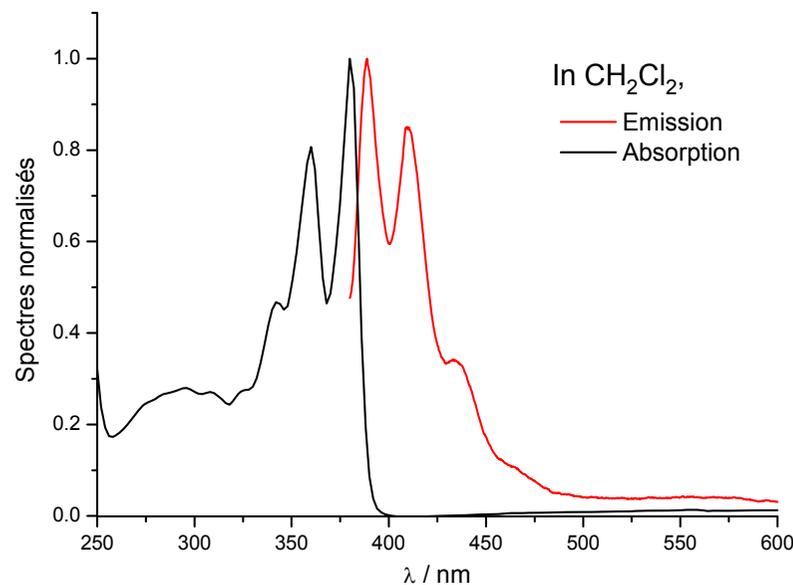
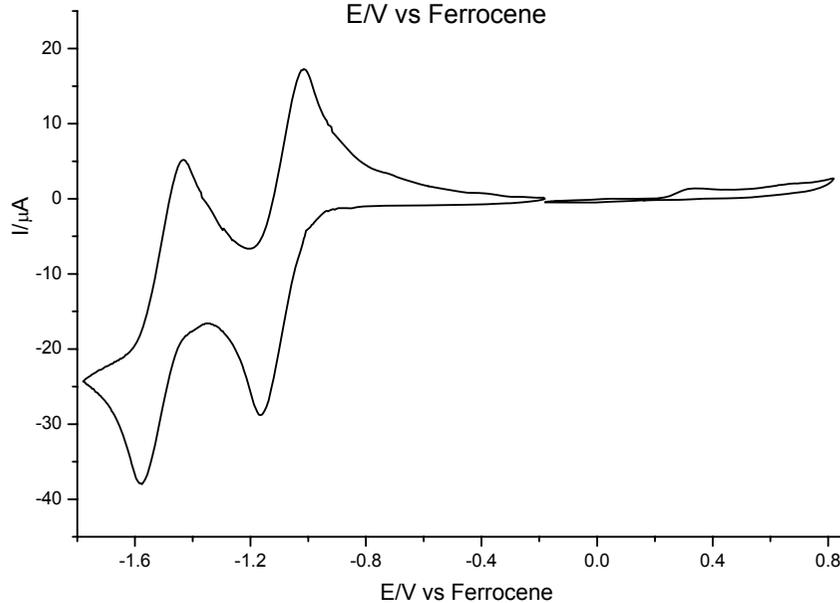
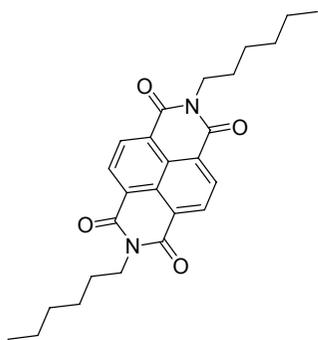
R = CH=CH₂, CH₂SH

Electron acceptor (n-type)

Optics and redox properties of the conjugated systems



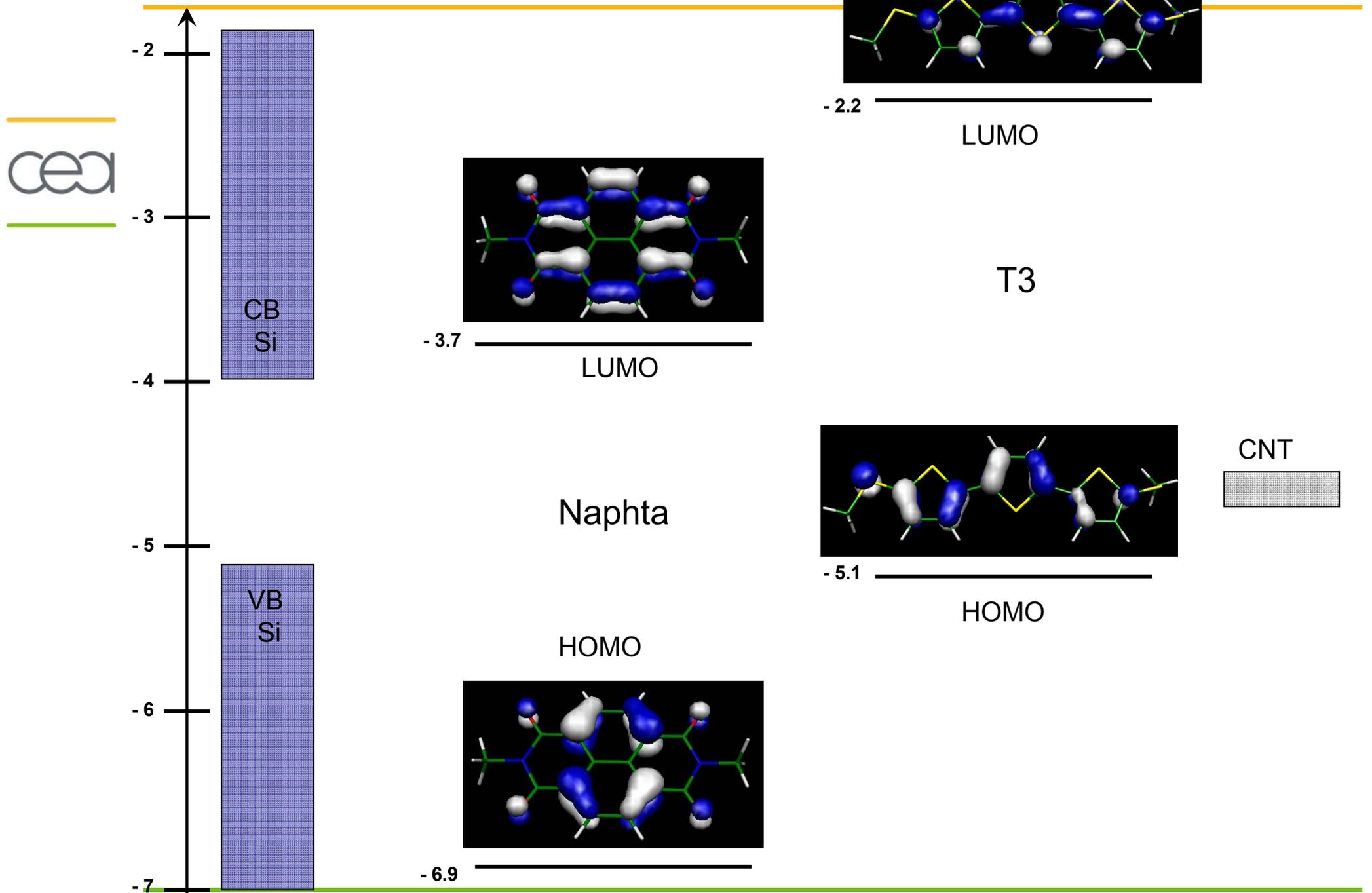
Optic Gap : 432 nm \Rightarrow 2.9 eV



Optic gap : 384 nm \Rightarrow 3.2 eV

vs.	E _{ox/red1} /V ¹			E _{ox/red1/2} ²		
	Ag/AgNO ₃ (10 mM)	Fc ⁺ /Fc	SCE	Ag/AgNO ₃ (10 mM)	Fc ⁺ /Fc	SCE
3T	0.520 V	0.430 V	0.820 V	0.663 V	0.573 V	0.960 V
Napht	-0.990 V	-1.080 V	-0.690 V	-1.410 V	-1.500 V	-1.110 V

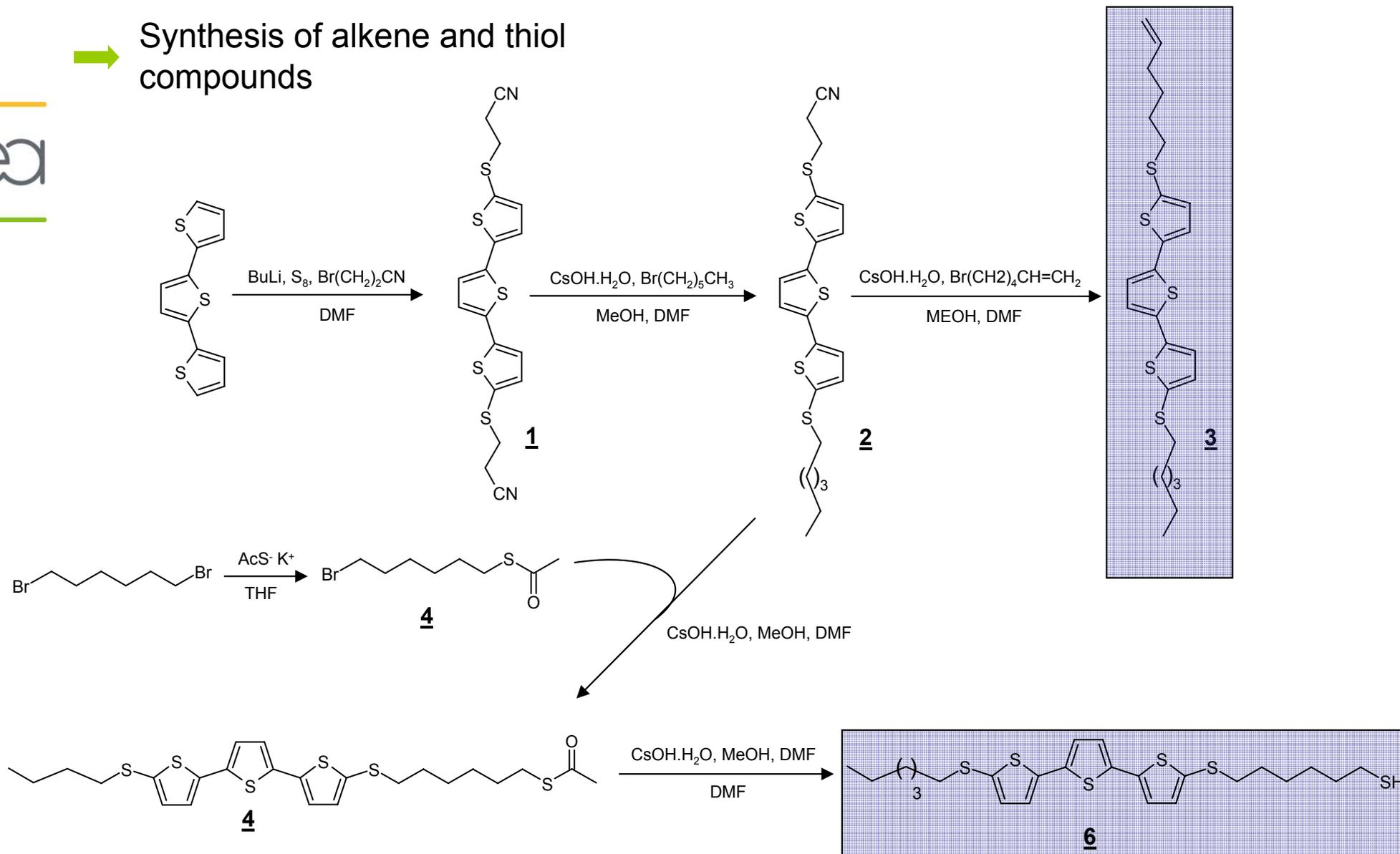
Energy level of the compounds targeted



Synthesis of p-type compound : Terthiophene derivative (3T)

Synthesis of alkene and thiol compounds

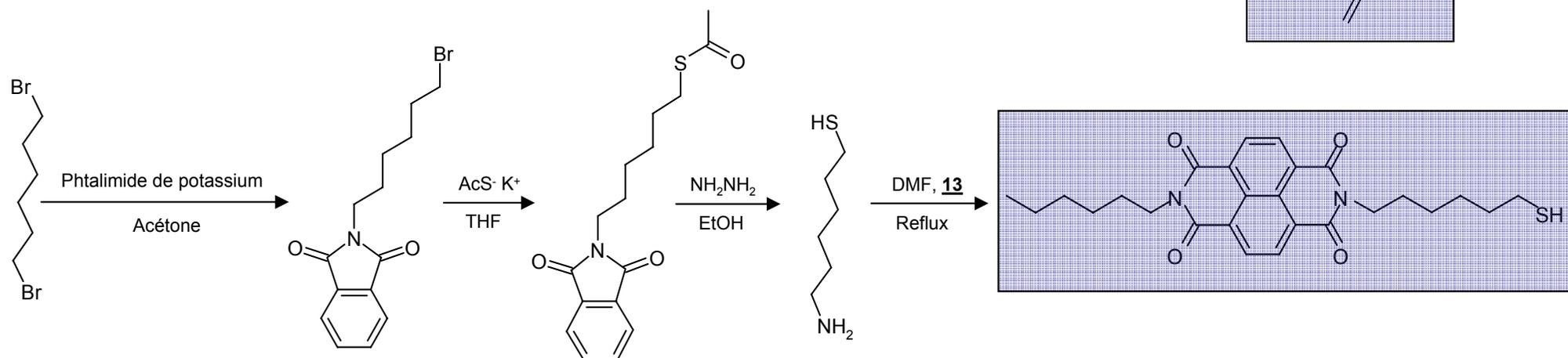
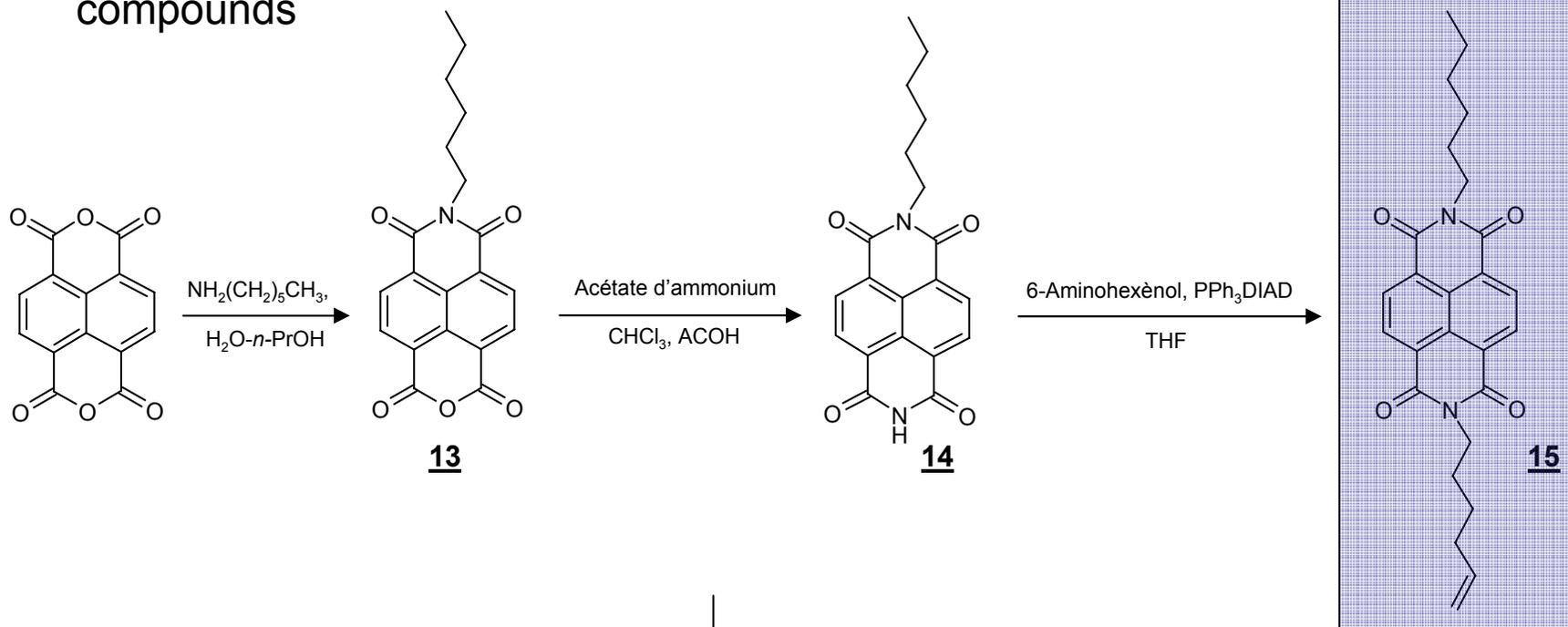
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Synthesis of n-type compound : Naphthalene tetracarboxiimide (Naph)

Synthesis of alkene and thiol compounds

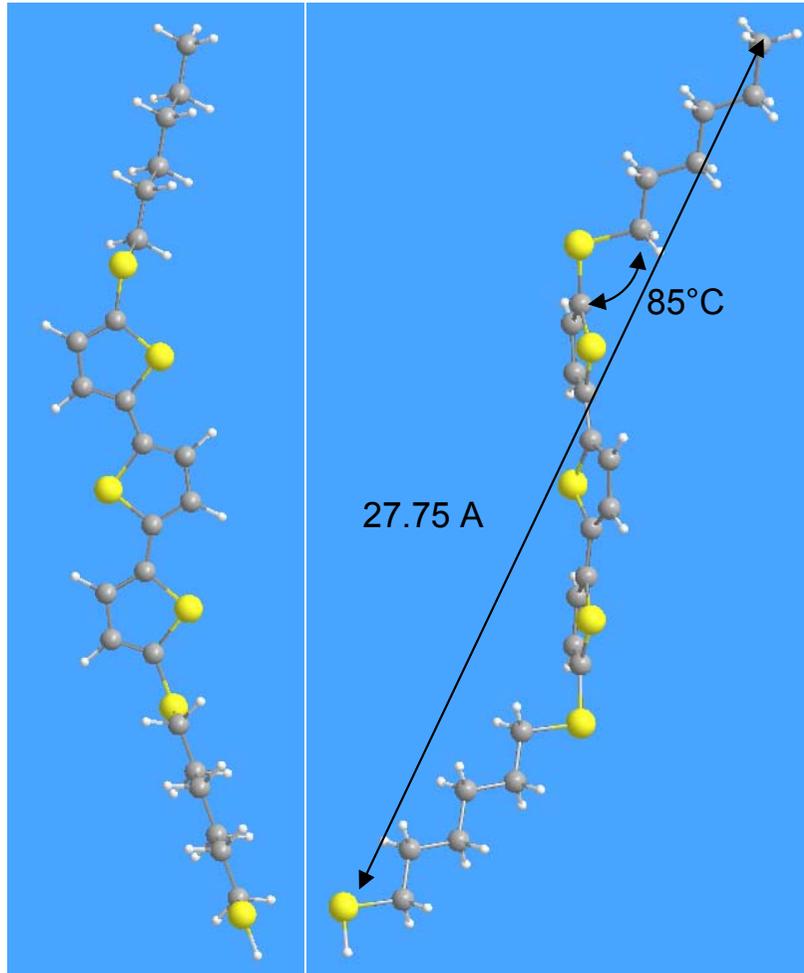
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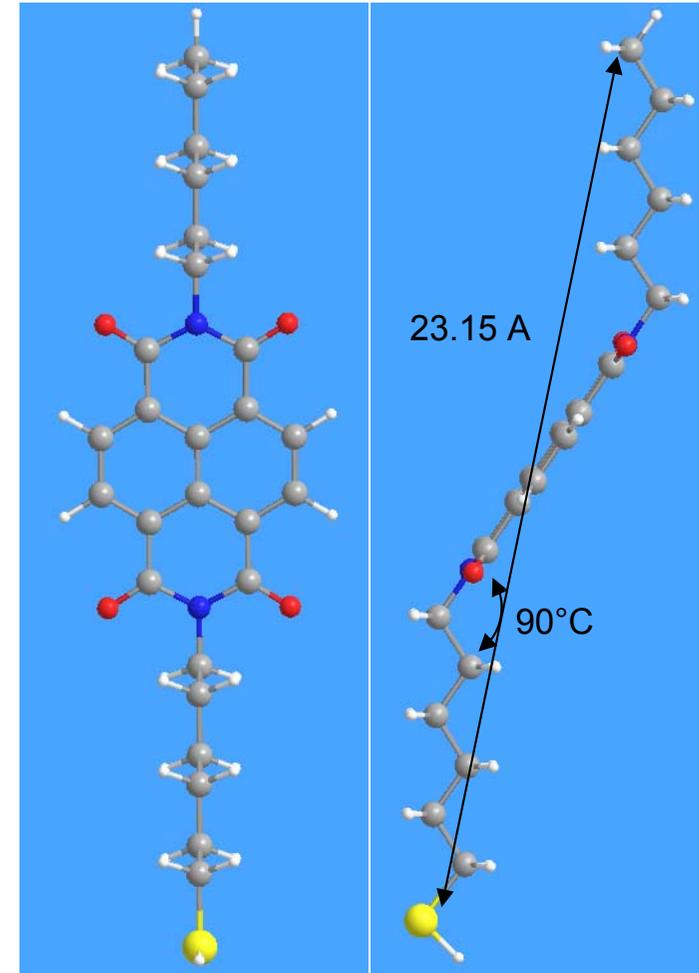
Geometries optimisation of 3T and Naph thiols derivatives

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3TSH



NaphSH



Gaussian 98 DFT (Becke3lyp), Bases : 6-31G*.

SAMs on gold

→ Conditions

Thiol Concentration : 10^{-3} M

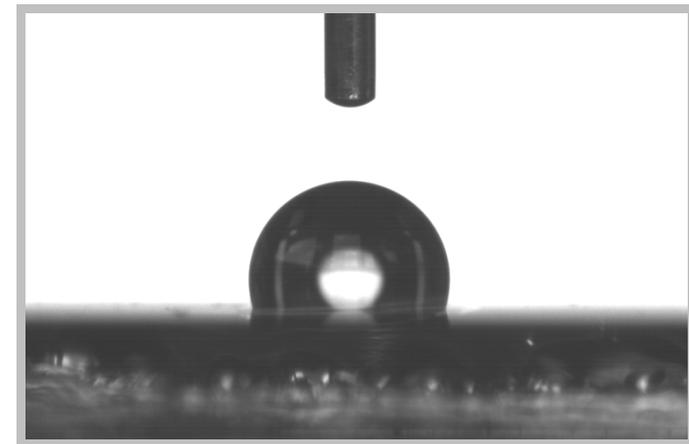
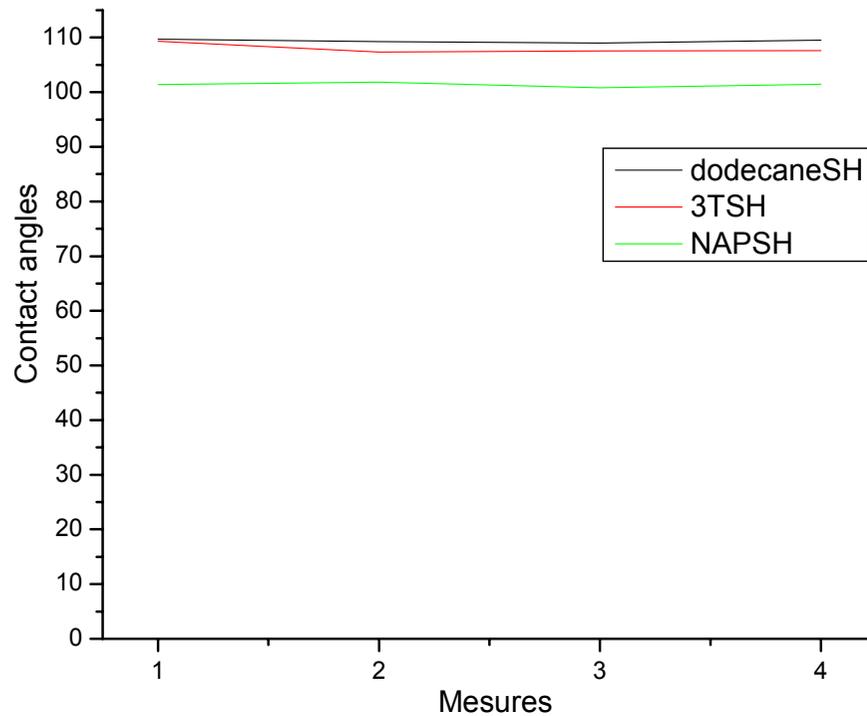


Solvent : Methylene Chloride/Ethanol

Reaction time : 24 hours

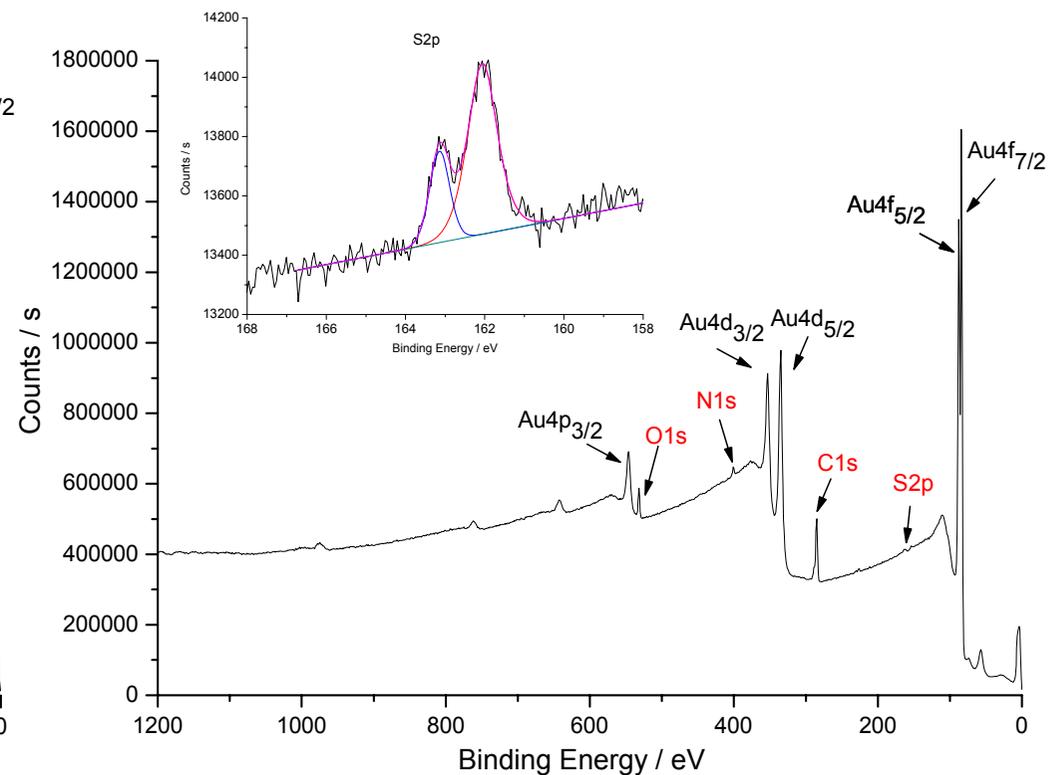
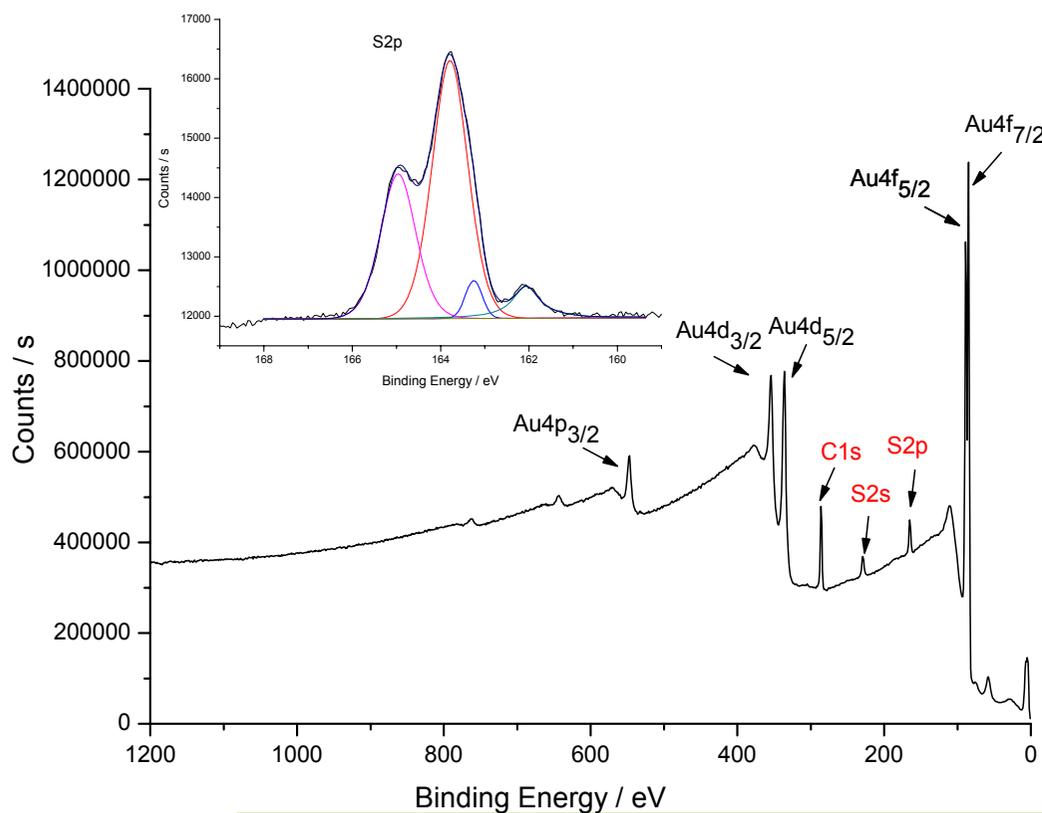
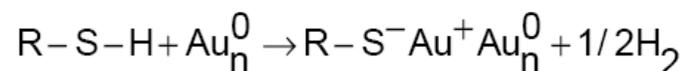
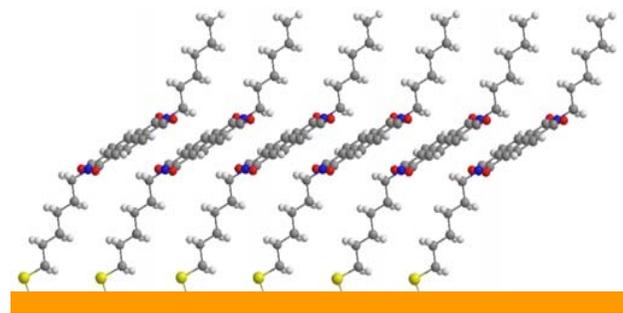
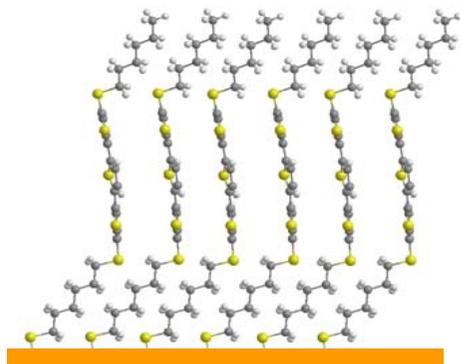
$\theta \approx 100 - 110^\circ$

→ Contact angle measurements

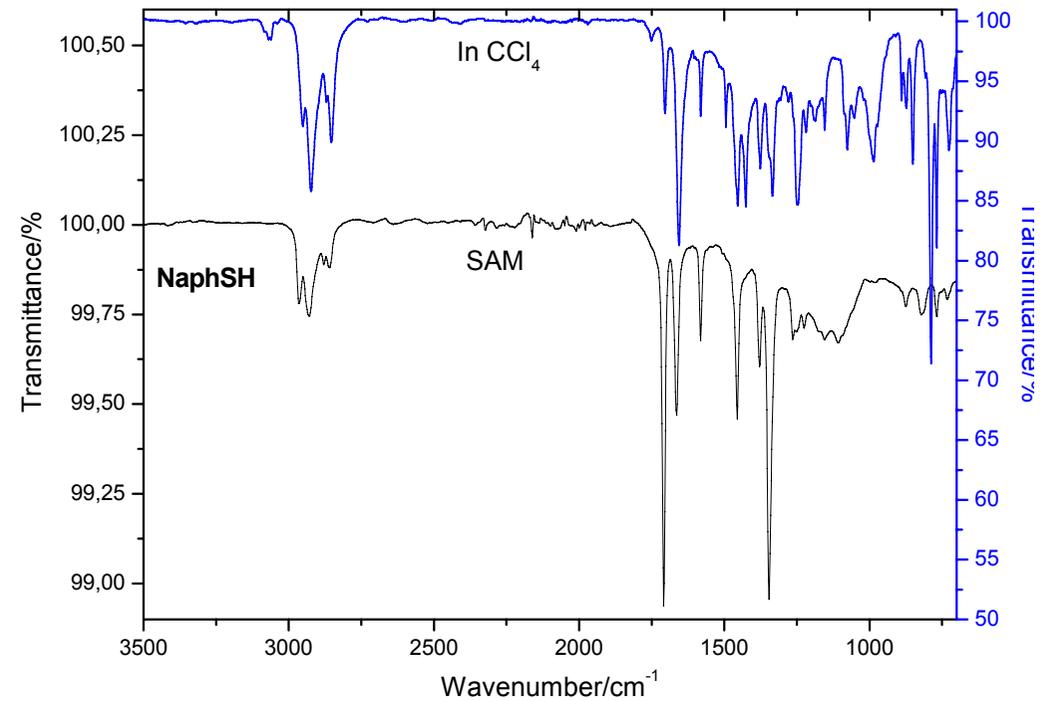
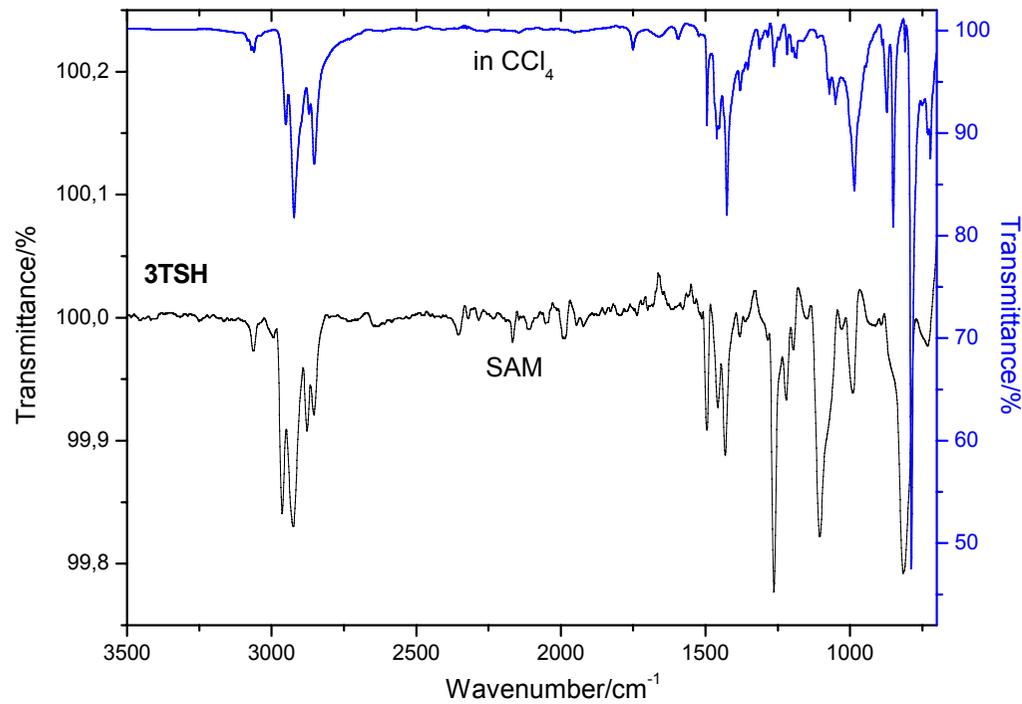
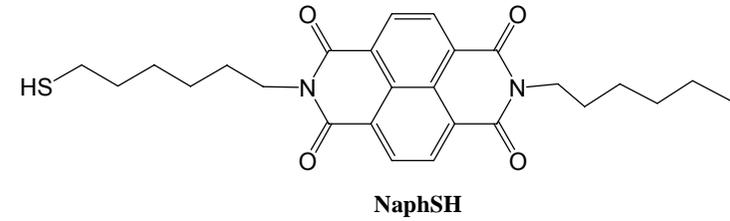
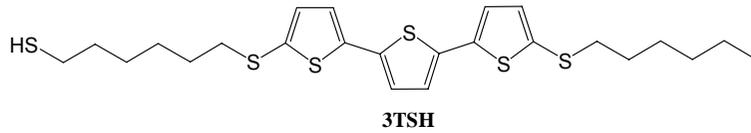


3T-SH

XPS analysis of SAMs on gold

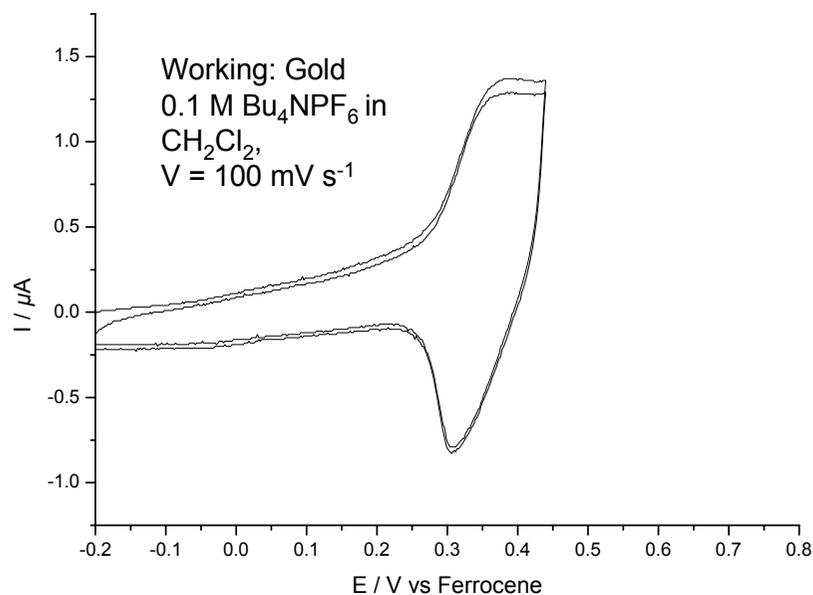
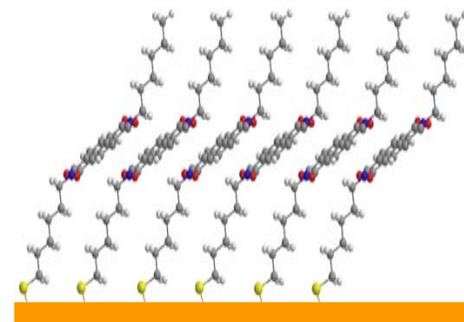
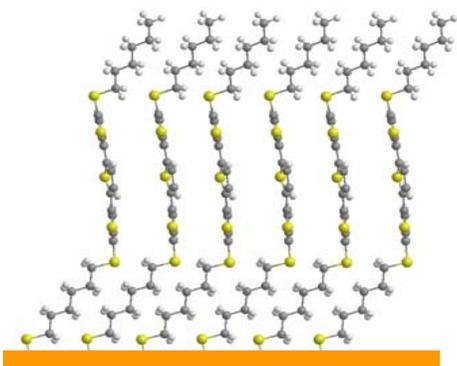


FT-IR analysis of SAMs on gold



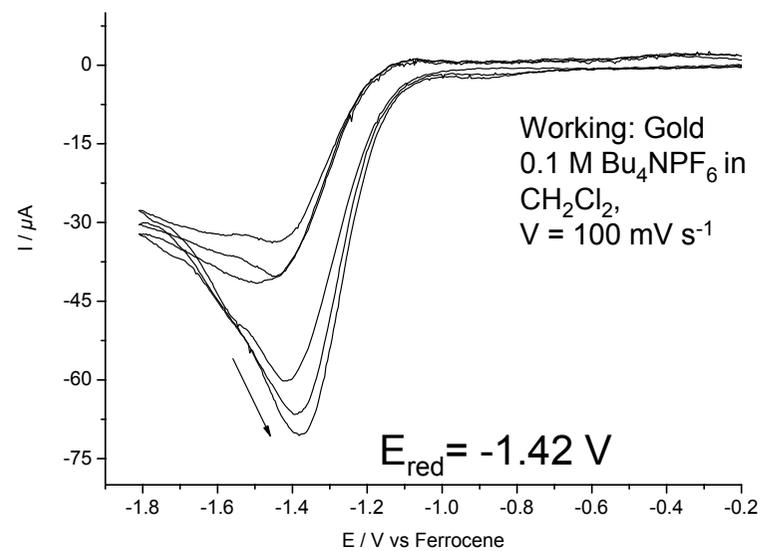
Cyclic voltamperometry of a SAM of 3TSH on gold

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$E^{\circ}_1 = 325 \text{ mV}$ Versus ferrocene
 $\neq -110 \text{ mV}$ / in solution

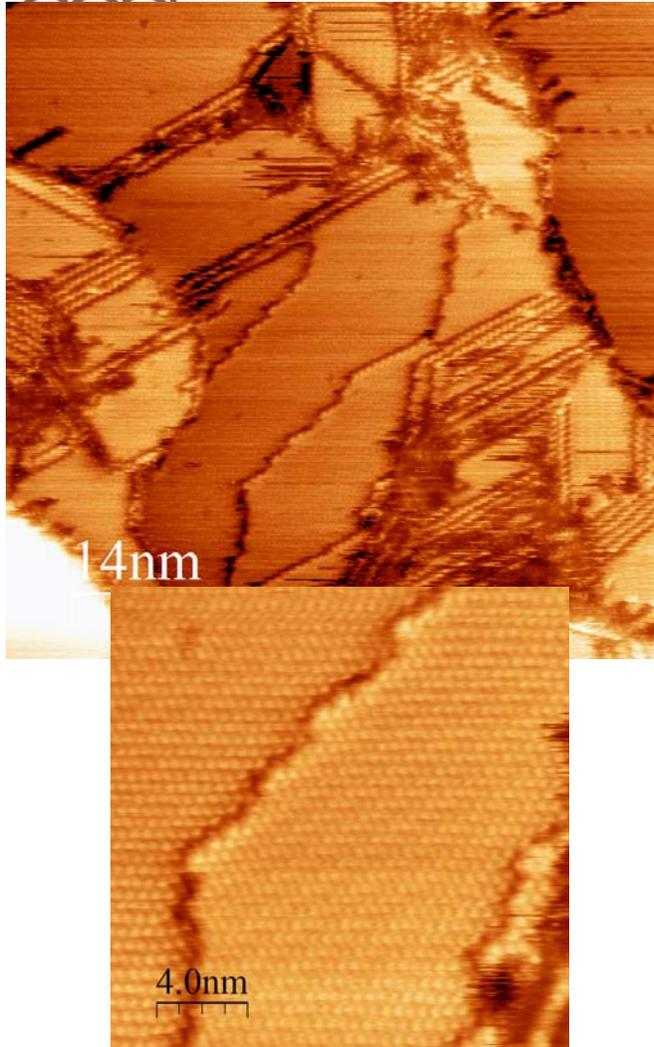
➡ $\pi - \pi$ interactions



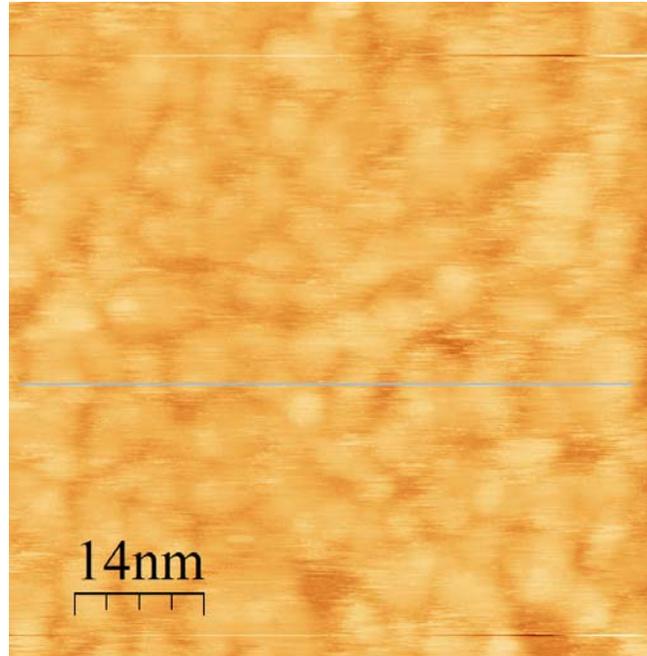
$\neq -200 \text{ mV}$ / in solution
Dimerization, Thiolate, Alkyl Chain

Morphology of the SAMs - STM

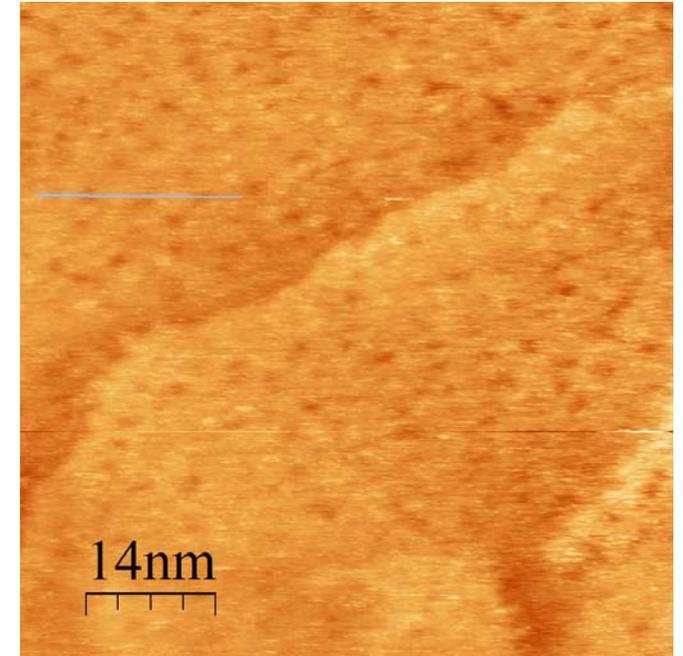
DodecaneSH



3TSH

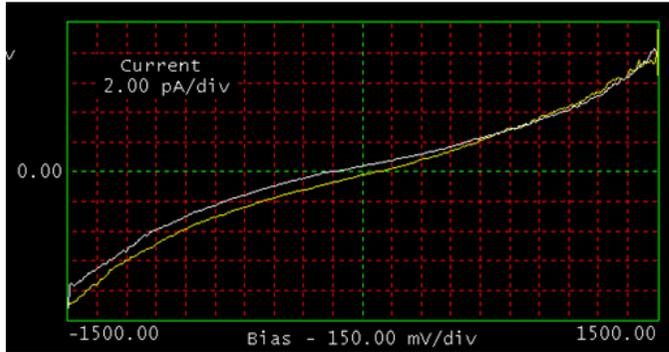


NaphthSH

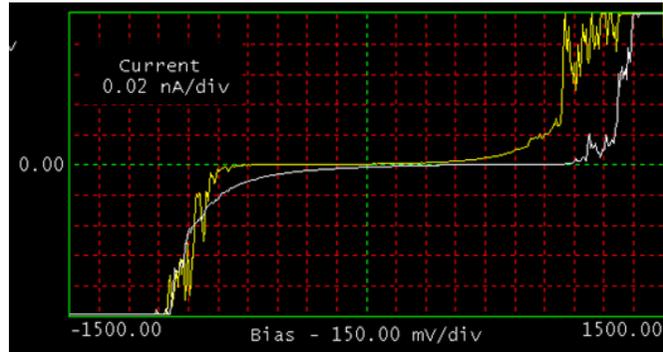


I/V measurements - STM

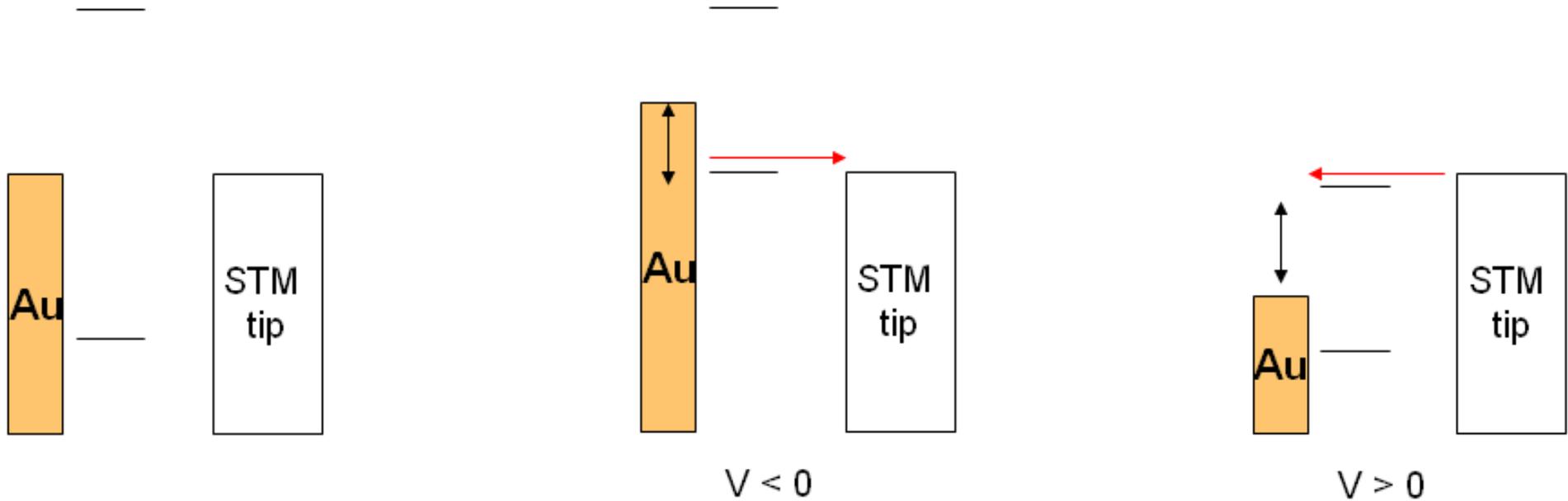
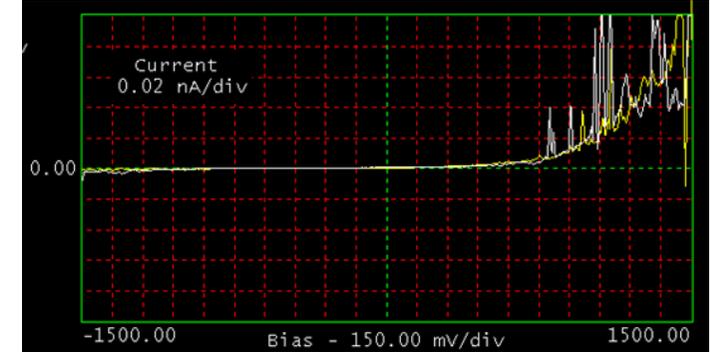
DodecaneSH



3TSH



NaphthSH

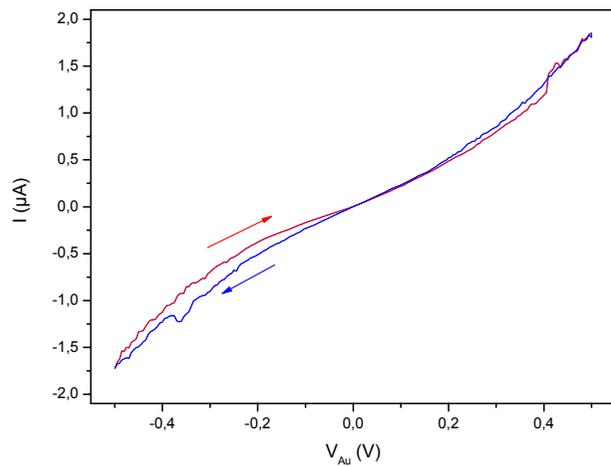


Contact with InGa Eutectic and I/V measurements

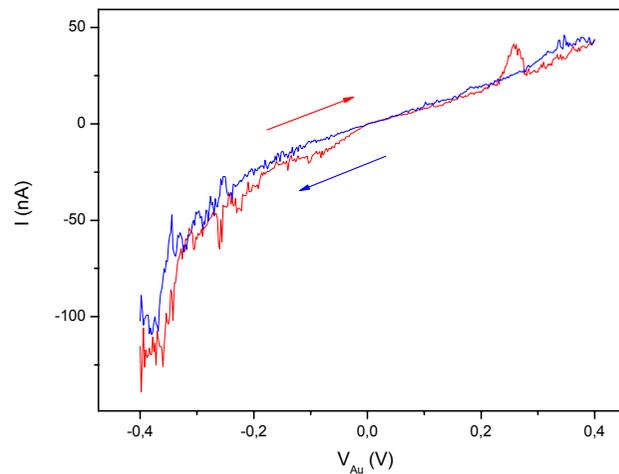
- Whitesides & al. , *Angew.Chem.Int.Ed.* **47**, 142 [2008]



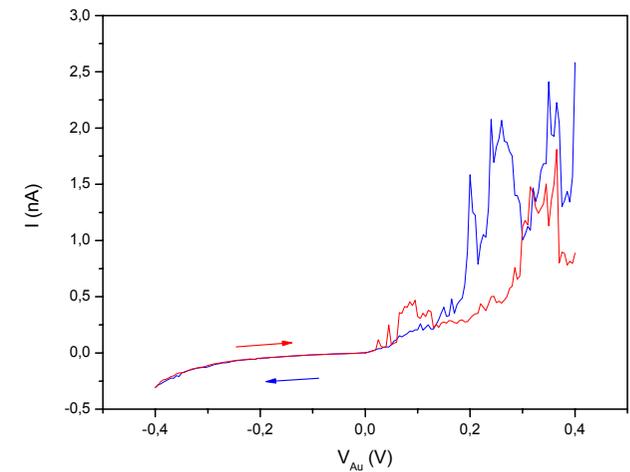
DodecaneSH



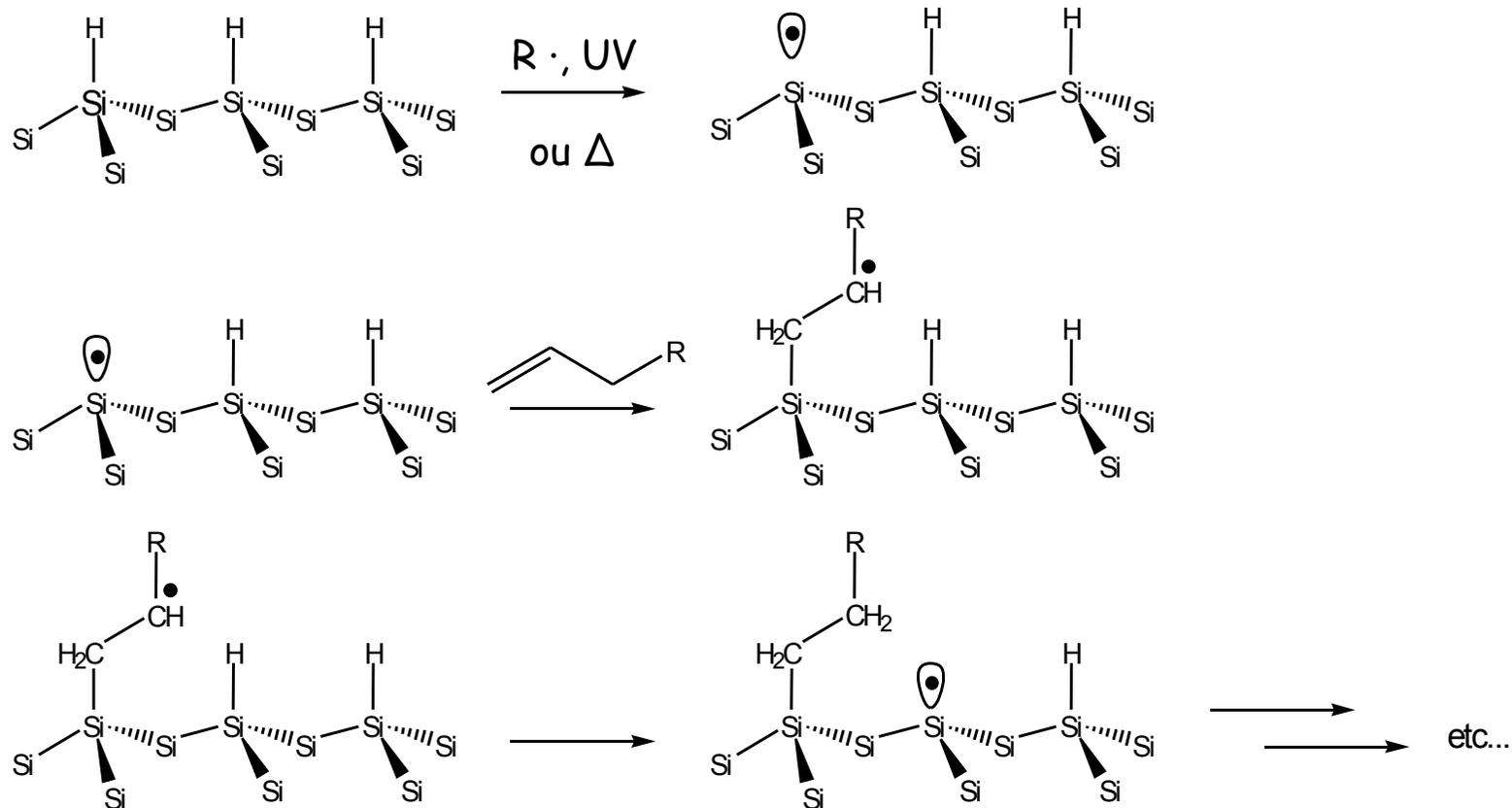
3TSH



NaphthSH



Hydrosilation reaction mechanism on SiH



Grafting of the alkenes compounds on silicon

Different ways were tested for the 3T derivative:



↗ *Sublimation* → sublimation impossible

↗ *Dilution* → re-oxidation of the silicon

↗ *Irradiation* → degradation

➡ **Grafting Neat**

Different ways were tested for the Naphth derivative:

↗ *Sublimation* → sublimation impossible

↗ *Neat* → mp > 200°

↗ *Dilution* → re-oxidation of the silicon

➡ **Grafting Neat**

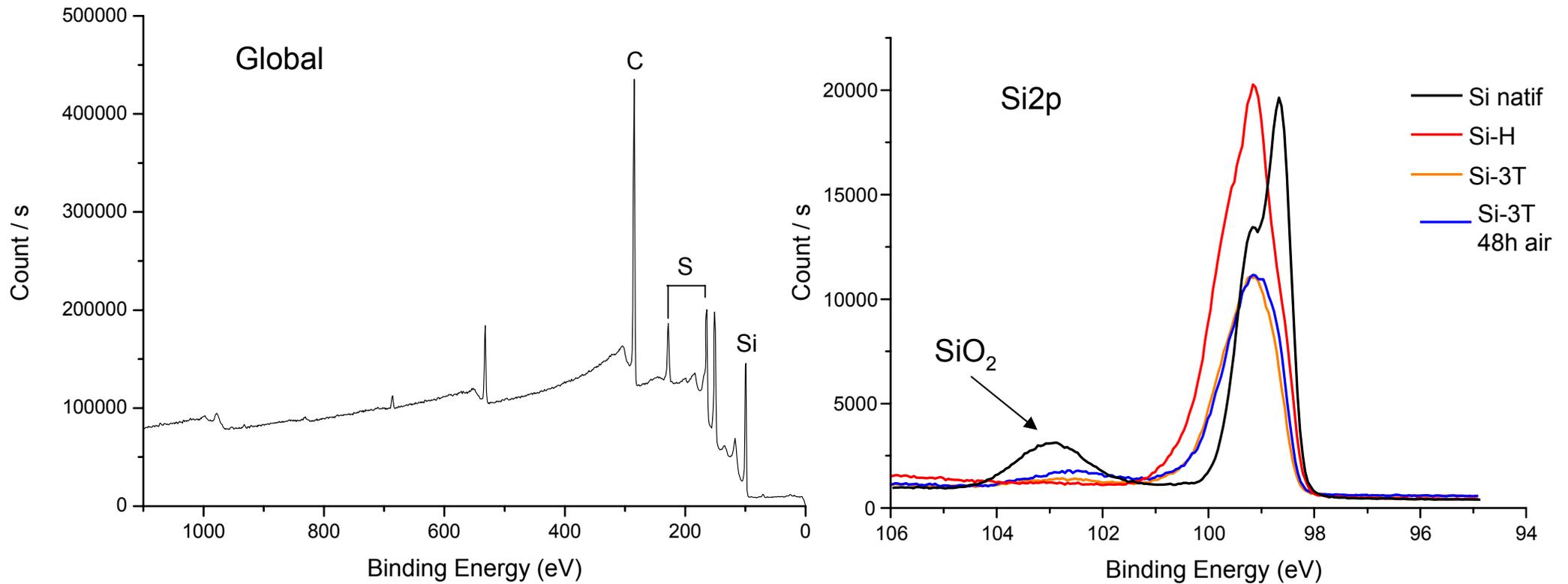
Grafting of the 3T on silicon p++ (100)

Conditions : Neat, 150°C, under vacuum, 12H



Contact angle of 105°

XPS :



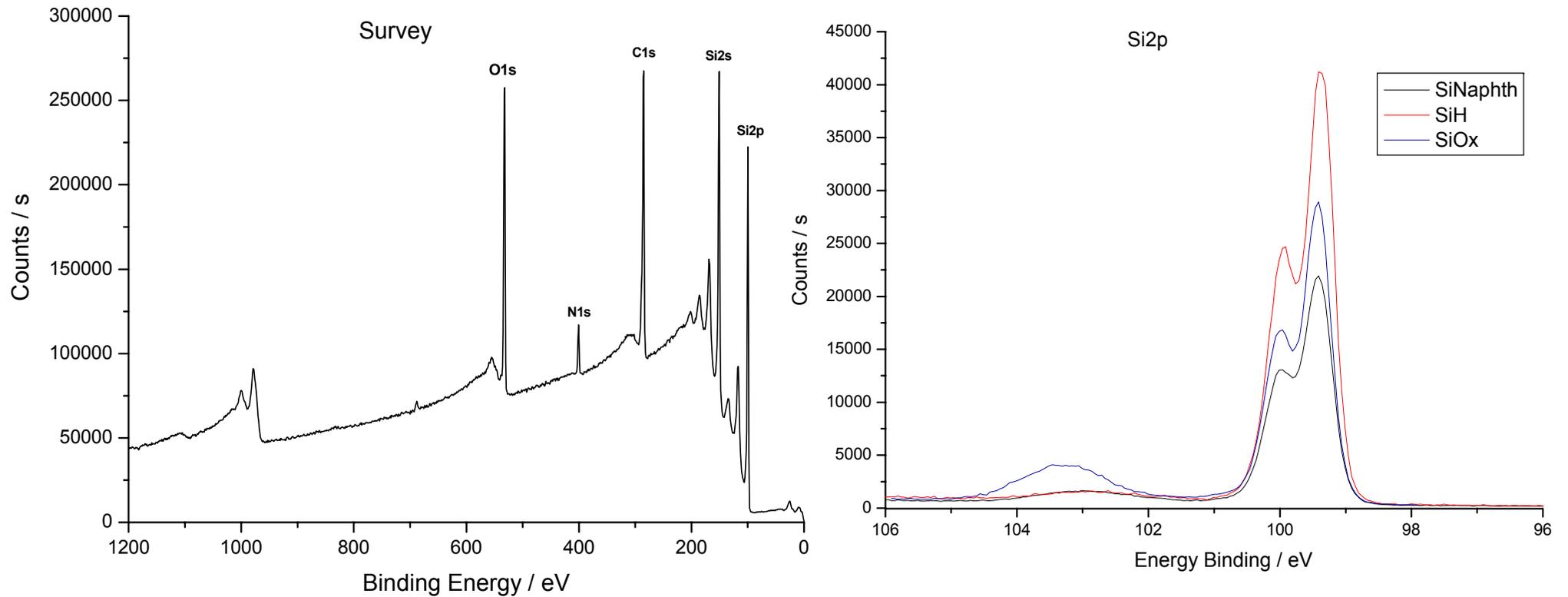
Grafting of the Naph on silicon n++ (111)

Conditions : Neat, 220°C, 2H, under vacuum (10^{-7} mbar)

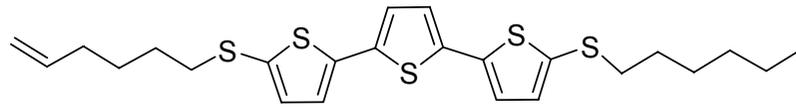


Contact angle of 100°

XPS analysis:

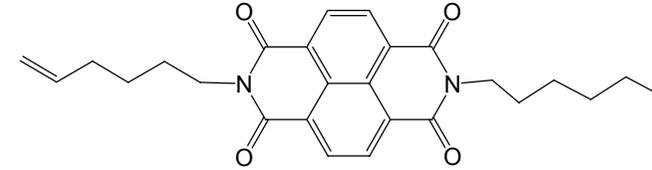
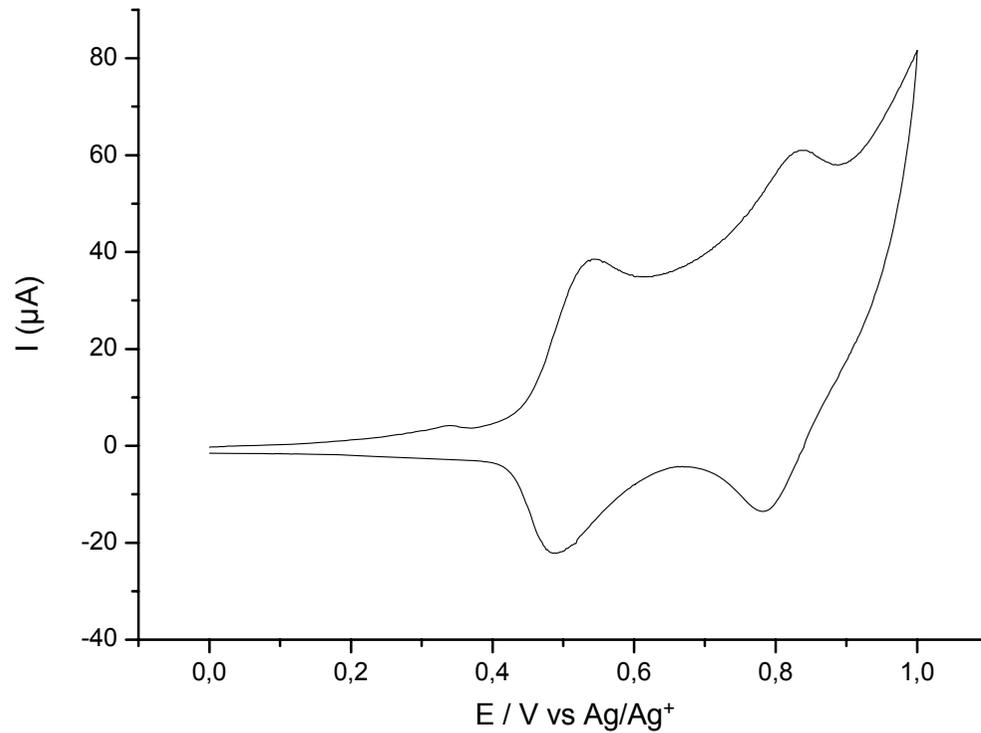


Cyclic Voltamperometry



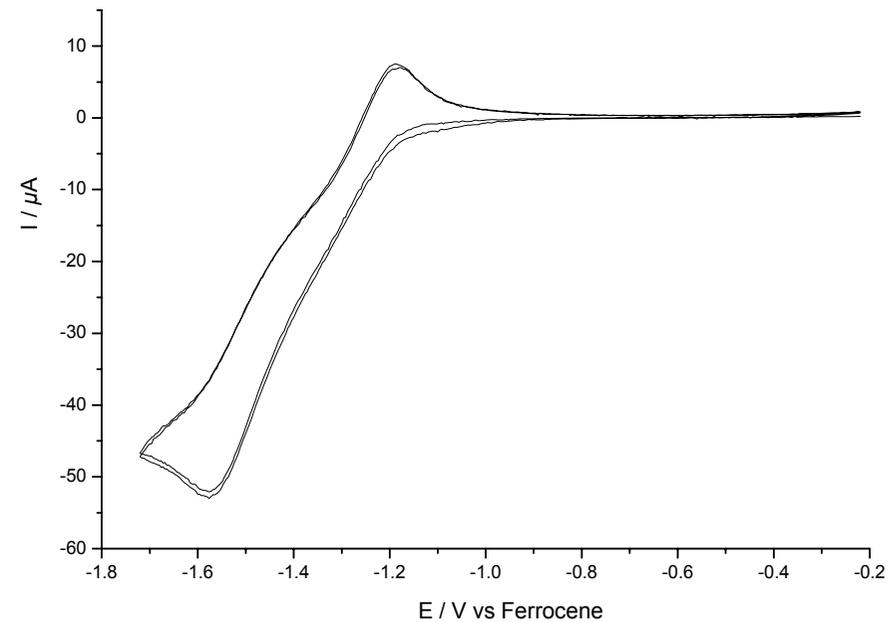
3TAL

On Si(100)-P⁺⁺ CH₂Cl₂,
TEAP (0.1M), 100 mV.s⁻¹



NaphAL

Working: Silicon 111 n⁺⁺
0.1 M Bu₄NPF₆ in CH₂Cl₂,
 $V = 100 \text{ mV s}^{-1}$

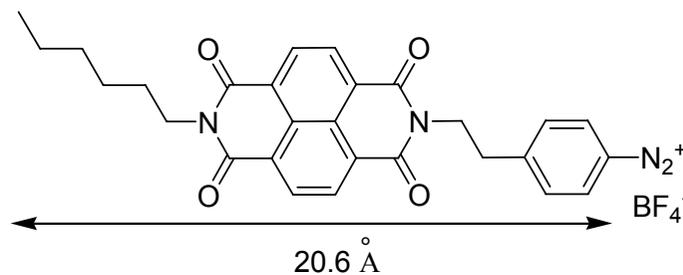
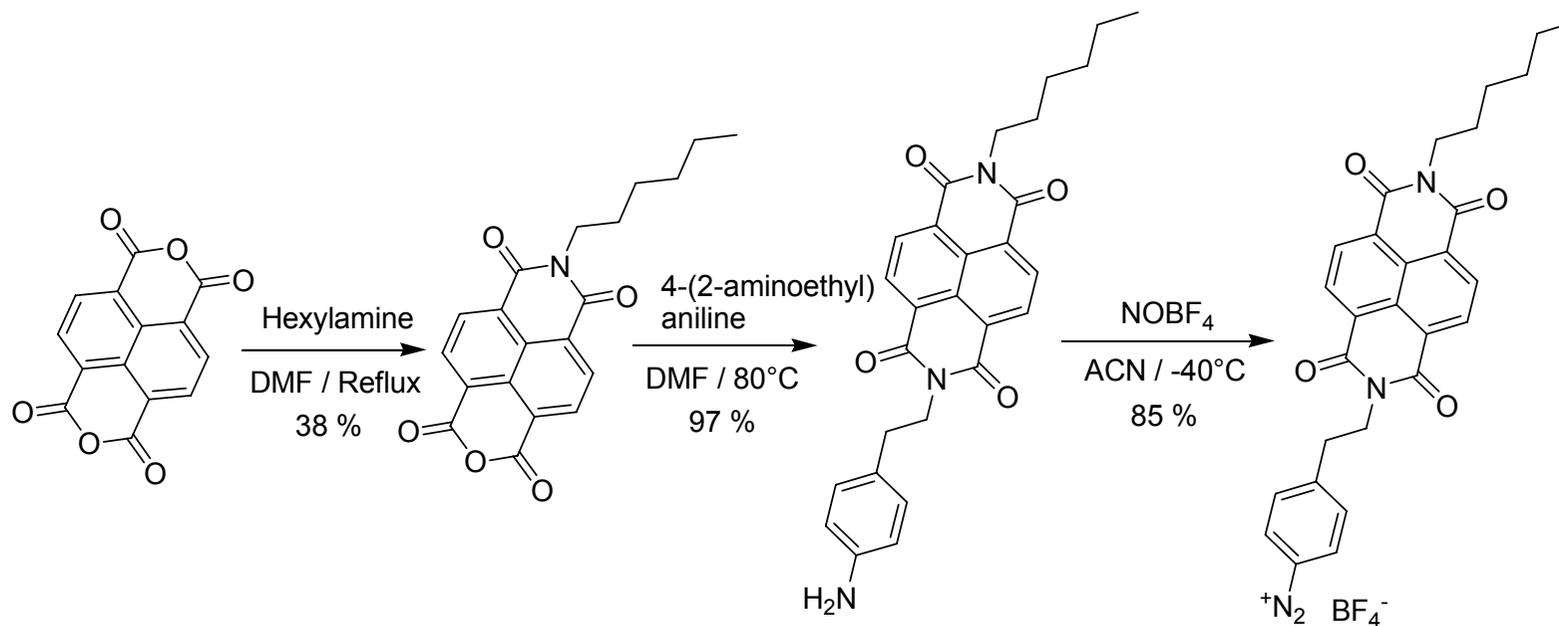


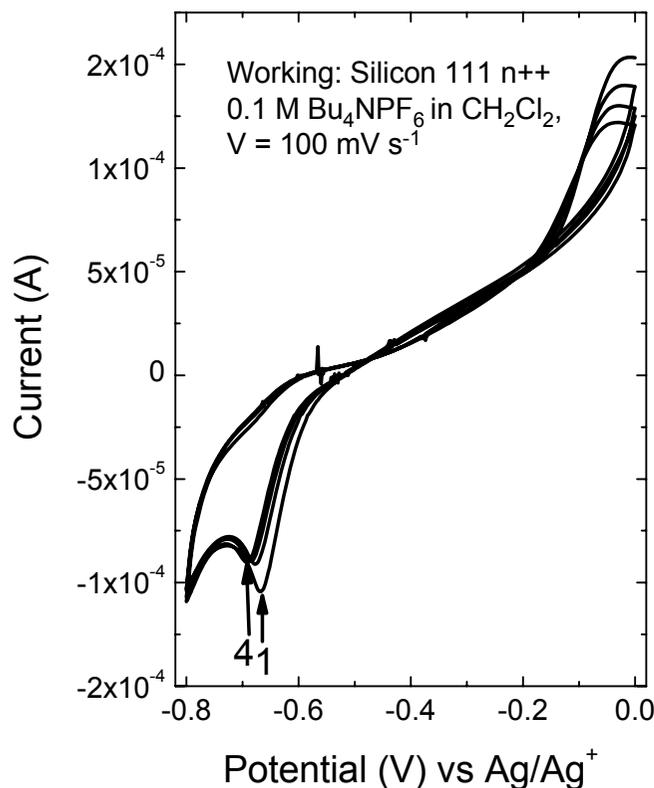
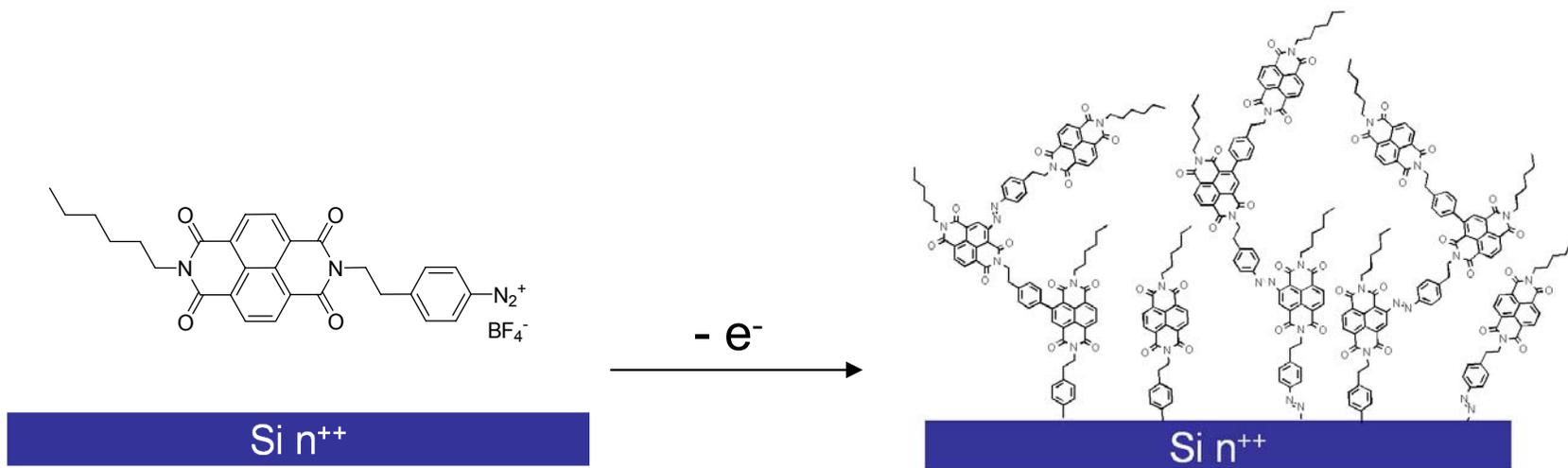
Conclusion of the first part



- Synthesis of two new σ - π - σ compounds with Thiol or alkene functions
- Monolayers on gold and on silicon (Contact angle, XPS, infrared spectroscopy, STM).
- NaphSH has a better packing than 3TSH on gold.
- I/V measurements on gold (STM and Eutectic InGa) next on silicon

Synthesis of
***N*-(2-(4-diazoniophenyl)ethyl)-*N'*-hexylnaphthalene-1,8:4,5-tetracarboxydiimide tetrafluoroborate**



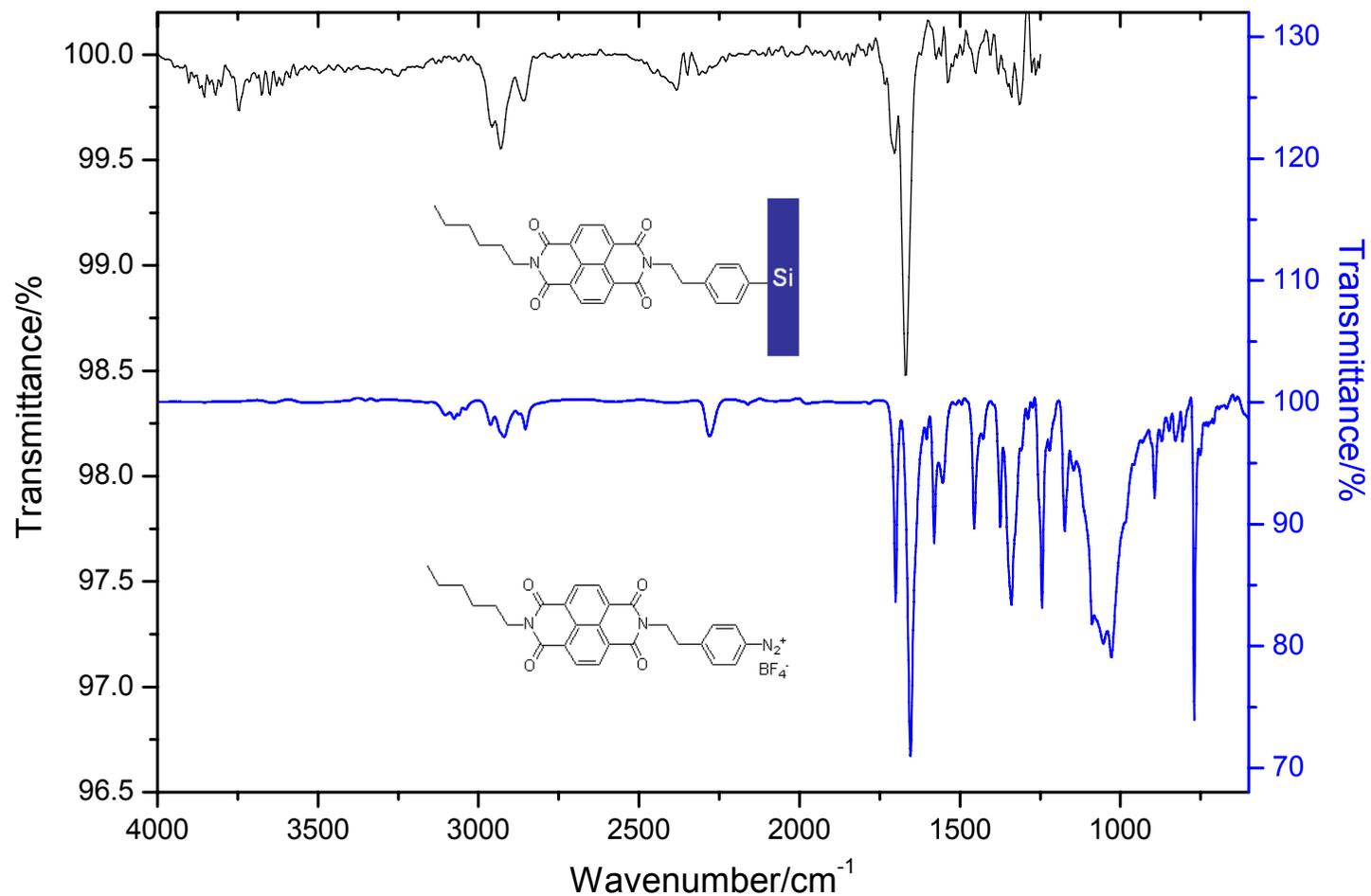


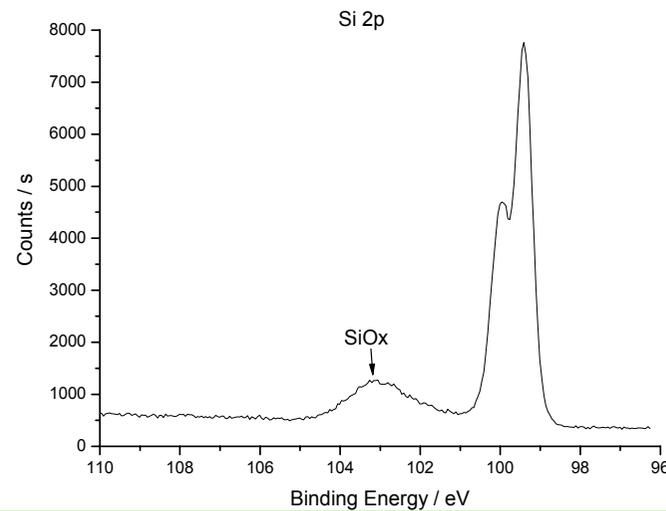
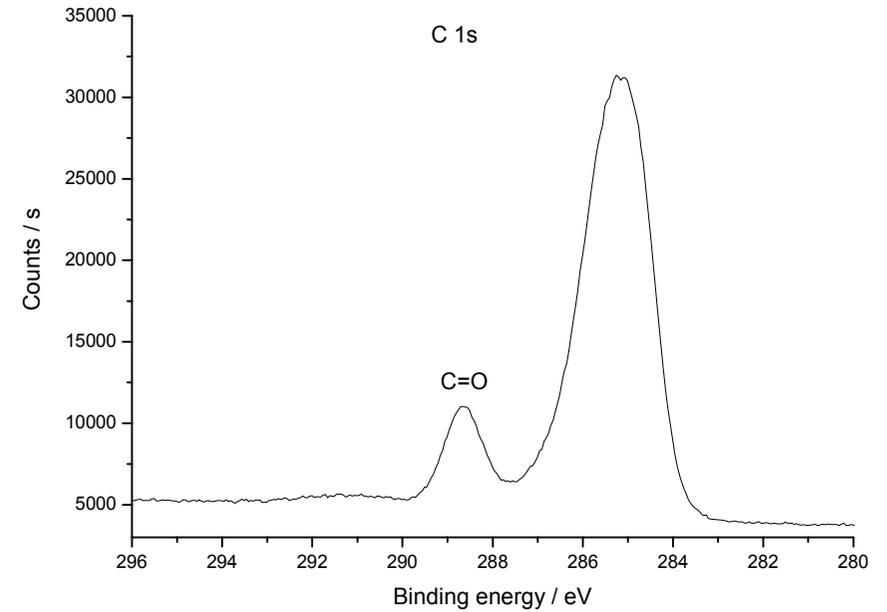
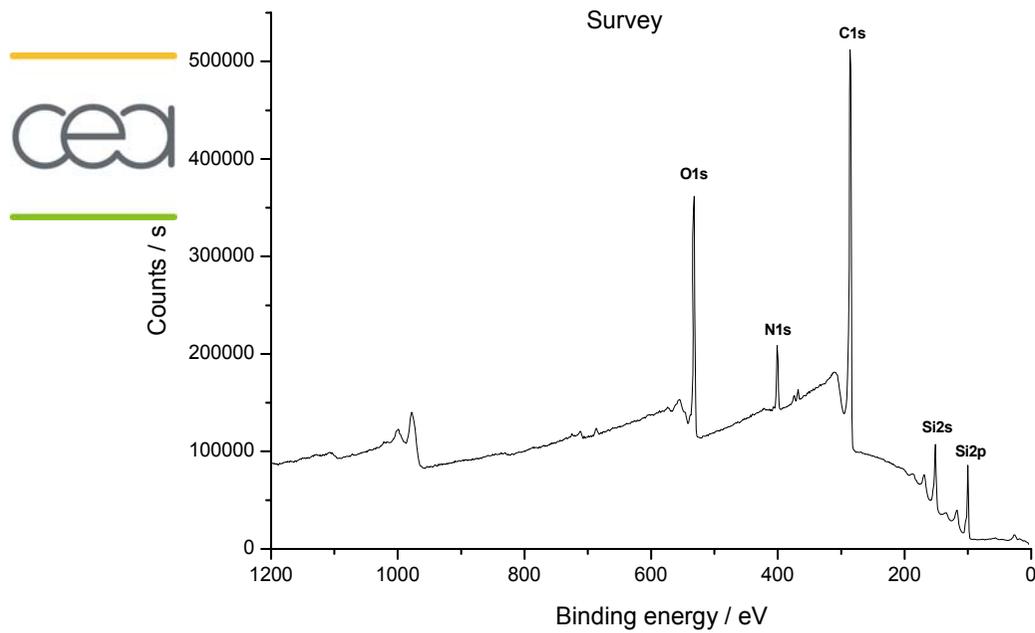
CV recorded using diazonium salt of $\sigma-\pi-\sigma$ molecules using H-terminated Si (111) as working electrode. Note the shift in the irreversible peak to higher potentials with increasing number of scans.

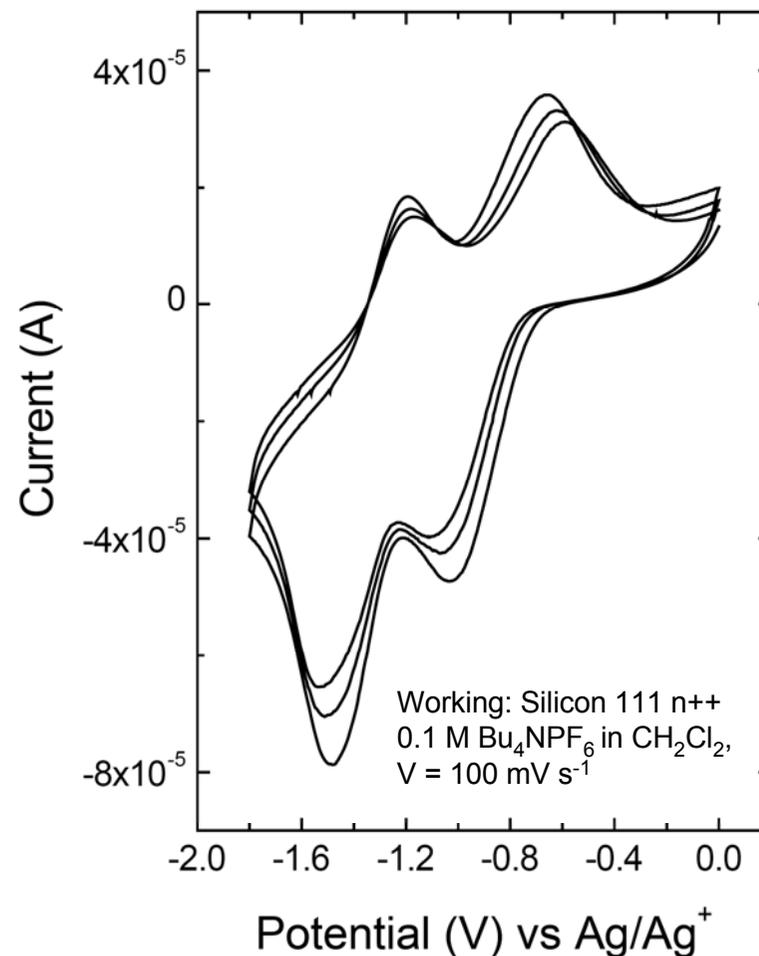


- Contact Angle : 70°

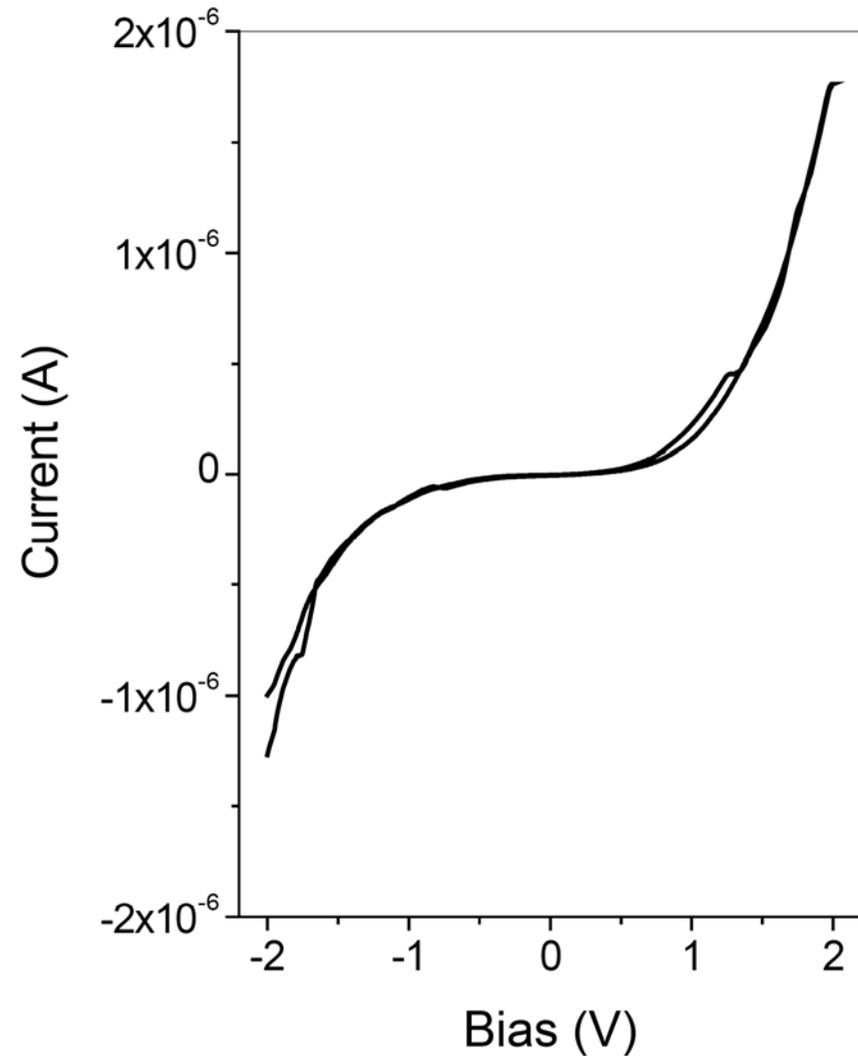
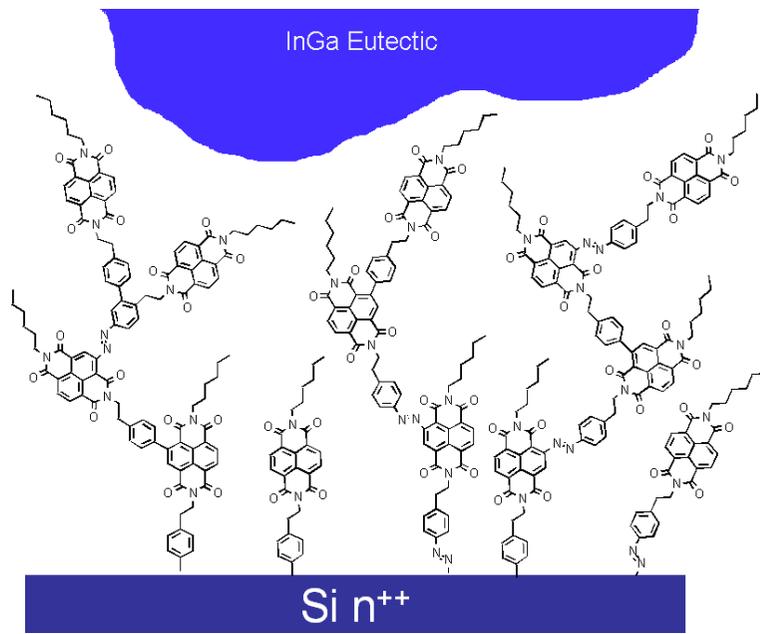
- Infrared spectrum







CV recorded for the electrografted organic layers on Si grafted using the reduction of diazonium salt.



Current-voltage characteristic of the σ - π - σ layers (12 nm) grafted on Si using diazonium salt

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the end

